OPTICAL INTERCONNECT AND METHOD FOR MAKING THE SAME

ABSTRACT OF THE DISCLOSURE

A method of fabricating an integrated optical interconnection includes forming a first optical waveguide in a semiconductor substrate, forming a first layer of dielectric material disposed above the optical waveguide, forming an optical interconnect in the first dielectric layer and disposed proximate to the first optical waveguide. The method further includes forming a second layer of dielectric material disposed above the optical interconnect, forming a second optical waveguide in the second layer of dielectric material and disposed proximate to the first optical waveguide, and forming a conductive contact disposed above and proximate the second optical waveguide.